



JRW

PATENT
Customer No. 22,852
Attorney Docket No. 04329.3300

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)
Takashi Sato et al.) Group Art Unit: 2829
Application No.: 10/814,303) Examiner: NGUYEN, Jimmy
Filed: April 1, 2004)
For: EXPOSURE METHOD,) Confirmation No.: 8598
EXPOSURE QUANTITY)
CALCULATING SYSTEM USING)
THE EXPOSURE METHOD AND)
SEMICONDUCTOR DEVICE)
MANUFACTURING METHOD)
USING THE EXPOSURE)
METHOD)

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

RESPONSE TO RESTRICTION REQUIREMENT

In a restriction requirement mailed October 3, 2005, the period for response to which extends through November 3, 2005, the Examiner required restriction under 35 U.S.C. § 121 between Group I, claims 1-13, characterized by the Examiner as being drawn to a method and system of exposing the quantity of calculate; and Group II, claims 14-20, characterized by the Examiner as being drawn to a method of manufacturing semiconductor device. Applicants elect to prosecute Group I, claims 1-13, without traverse.

Please grant any extensions of time required to enter this response and charge
any additional required fees to our deposit account 06-0916.

Respectfully submitted,

FINNEGAN, HENDERSON, FARABOW,
GARRETT & DUNNER, L.L.P.

Robert E. Conner J # 274132
By: *for Richard V. Burgujian*
Richard V. Burgujian
Reg. No. 31,744

Dated: November 2, 2005